

PATENT
8075-1007

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Rikizo HATAKEYAMA et al.

Conf. Unknown

Application No. 10/528,561 ✓

Group Unknown

Filed March 21, 2005

METHOD FOR PRODUCING ENDOHEDRAL
FULLERENES AND DEVICE THEREFORINFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

June 21, 2005

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the cited documents are made of record on the enclosed PTO Form-1449.

A concise explanation of the relevance of these items is that these references were cited in the corresponding International Application Serial No. PCT/JP03/12098, filed September 22, 2003.

Respectfully submitted,

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RJP/mjr
 June 21, 2005

**INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

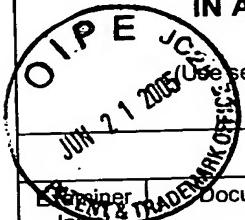
Attorney Docket No.:
8075-1007

Application No.:

Applicant:
HATAKEYAMA et al.

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**Group Art Unit:
Unknown**



(several sheets if necessary)

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

- Hatakeyama, R. et al., "Characteristics and Applications of Fullerene Plasmas", 6 Fullerenes Plasma no Seishitsu to Oyo", Journal of Plasma and Fusion Research, 1999, Vol. 75, No. 8, pp. 927-933.
Hatakeyama, R. et al., "Formation of Alkali-and Si-Endohedral Fullerenes Based on Plasma Technology", Electrochemical Society Proceedings, 2001, Vol. 2001-11, pp. 341-348.
Hirata et al., "The K⁺-C₆₀-plasma for material processing", Plasma Sources Sci. Technol., 1996, Vol. 5, No. 2, pp. 282-292.

EXAMINER:

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* English language abstract provided for the Examiner's convenience